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The invention relates to the nanostructured materials production technology, in particular to methods for producing metal nanostructured membranes.

The method, according to the invention, comprises the deposition of a thin Au film on a semiconductor substrate and subsequent etching of the substrate. At the same time, the Au film is deposited on the substrate by electrochemical deposition in a pulsed mode, and substrate etching is carried out by anodizing.

Claims: 1

Fig.: 3